PRESS RELEASE

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Lasertec Releases PELMIS EPM200 EUV Pellicle Inspection System Supporting CNT Pellicles

Yokohama, July 11, 2025 - Lasertec Corporation today announced the release of EPM200, the latest model of its PELMIS Series designed to inspect particles on EUV pellicles[1]. EPM200 is capable of inspecting carbon nanotube (CNT) pellicles, which are highly anticipated next-generation EUV pellicles.

Lasertec has earned recognition from wafer fabs and mask shops worldwide for its timely provision of solutions addressing diverse EUV mask inspection needs. Amid the recent EUV market growth, the adoption of CNT pellicles is being explored, and the need for their inspection is increasing today.

EPM200 is designed to detect particles on the surface of CNT pellicles and automatically determine whether they are on the front or back side, a capability previously considered unachievable. It also features defect type classification and various other applications, making it a powerful quality control tool for CNT pellicle manufacturers and device makers.

Lasertec provides a wide range of EUV-related inspection systems that support various stages of EUV mask manufacturing and device production, serving blanks manufacturers, pellicle suppliers, and device makers. Some of the products Lasertec offers for EUV-related applications, aside from the PELMIS Series, are the ACTIS Series Actinic[2] EUV Patterned Mask Inspection System, the MATRICS Series Mask Inspection System, the BASIC Series EUV Mask Backside Inspection and Cleaning System, and the ABICS Series EUV Mask Blanks Inspection and Review System.

Lasertec will continue to offer new solutions that address the evolving needs of EUV lithography, facilitating further innovation and better quality control and delivering higher value to the semiconductor industry.

1: Pellicles are protective films attached to masks to prevent particle contamination.
2: Actinic refers to inspection light that matches the wavelength used in EUV lithography exposure.

Features

- EUV pellicle inspection and automatic determination of whether particles are on the front or back side
- Defect type classification and various other applications

Applications

- Incoming inspection of EUV masks with pellicles attached and periodic quality assurance inspection at wafer fabs
- Particle inspection and quality assurance in pellicle manufacturing process

PELMIS EPM200 EUV Pellicle Inspection System

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